

DATA SHEET

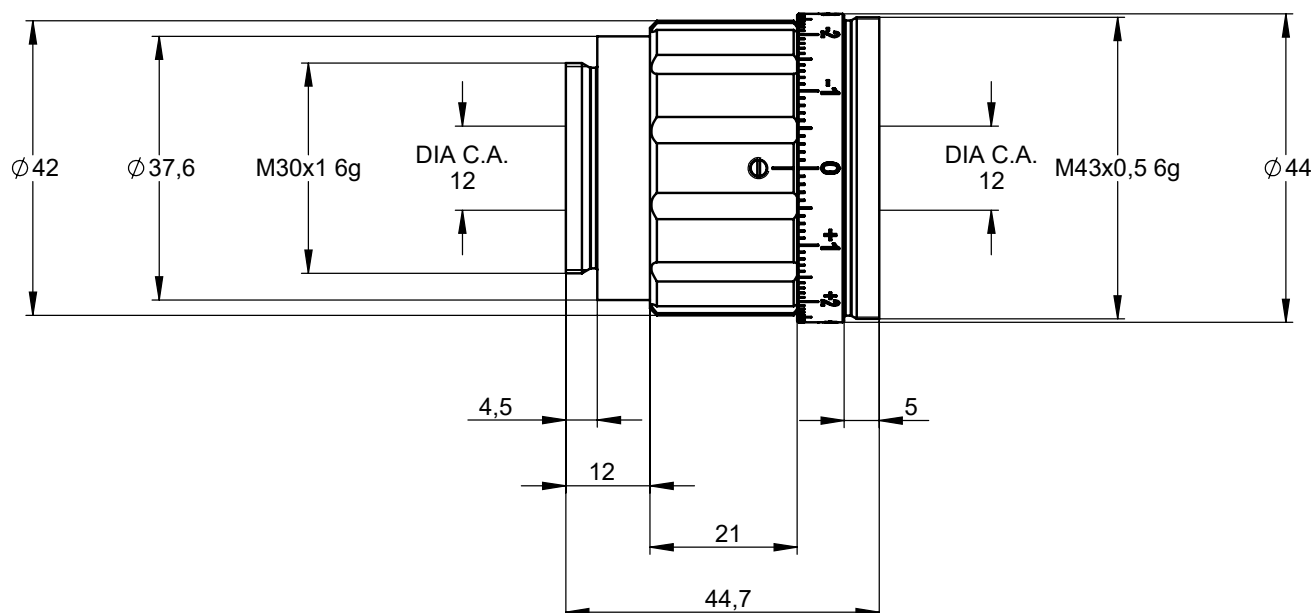


S6EXK0005-292

BEAMEXPANDER
MAGNIFICATION 0.5
FOR 515 - 545 nm
FUSED SILICA



OUTLINE DRAWING

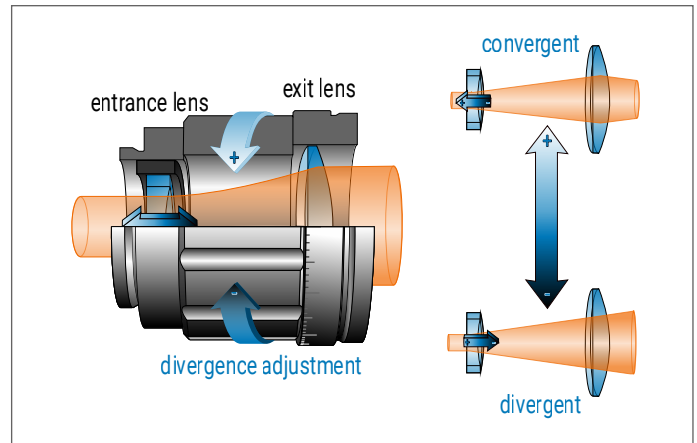


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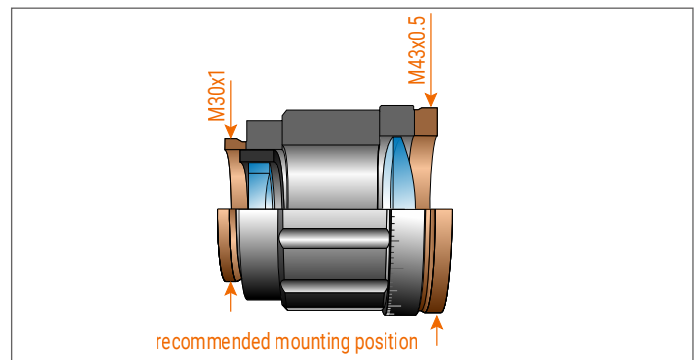
SPECIFICATIONS

article number	S6EXK0005-292
design wavelength [nm]	532
magnification factor	0.5
divergence adjustable	yes
optical principle	Galilei (no internal focus)
pointing stability [mrad]	< 1
clear input aperture [mm]	12.0
clear output aperture [mm]	12.0
recommended beam-Ø [mm] ¹⁾	10.0
total number of lenses	2
total transmission [%]	> 99
lens material	fused silica
LIDT (coating) [J/cm²]	2.5 J/cm² per 1ns pulse at 50Hz
SP and USP usable	yes
SP and USP usable, reversed usage	yes
mounting thread	M30x1
weight [kg]	0.3
accessory	S6MEC0127 - adapter M30x1 to C-mount

DIVERGENCE ADJUSTMENT



MOUNTING POSITIONS



REMARKS

¹⁾clipped at $1/e^2$; wavefront error on axis (PV) < $\lambda/10$ (value provided by design)

magnification (reversed mode) = 1 / magnification (regular mode)

divergence adjustment = 0 → collimated input beam results in collimated output beam

maximum divergence adjustment is ± 3 mm

RoHS compliant

length at divergence setting „0“ stated in the drawing - length extension of max. 3 mm is possible

BACK REFLECTION POSITION

back reflections [mm]	
30.7	
back reflections reverse [mm]	
24.88	
0.00	
0.00	

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